

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit 1752

In re application of	:	September 29, 2006
Wu-Song Huang et al.	:	Examiner: Geraldine V. Letscher
Serial No. : 10/537,259		
Filed: May 31, 2005	:	IBM Corporation
		Dept. 18G/Bldg, 300-482
Title: High Sensitivity Resist	:	2070 Route 52
Compositions For Electron-Based	:	Hopewell Junction, NY
Lithography	:	12533-6531

Amendment

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

The following amendment is submitted in response to the official action dated June 29, 2006.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on page 6 of this paper.